

FORM PTO-1449 (modified)
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| Atty. Dkt. No. | M# | Client Ref. |
| | 0307015 | P-1749.000-US |

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: TEN BERGE et al.

Appln. No.: New Herewith

Filing Date: December 1, 2003

Date: December 1, 2003 Page 1 of 1

Examiner: Unknown Group Art Unit: Unknown

U.S. PATENT DOCUMENTS

| Examiner's Initials* | Document Number | Date MM/YYYY | Name (Family Name of First Inventor) | Class | Sub Class | Filing Date (if appropriate) |
|-------------------------|--------------------|-----------------|---|-------|--------------|------------------------------------|
| | AR | | | | | |
| | BR | | | | | |
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| | DR | | | | | |
| | ER | | | | | |
| | FR | | | | | |
| | GR | | | | | |

FOREIGN PATENT DOCUMENTS

| FOREIGN PATENT DOCUMENTS | | | | | | Abstract | | Readily Available | | |
|--------------------------|----|-----------------|--------------|---------|---------------|----------|----------|-------------------|---------|----|
| | | Document Number | Date MM/YYYY | Country | Inventor Name | | Enclosed | No | Enclose | No |
| | HR | | | | | | | | | |
| | IR | | | | | | | | | |
| | JR | | | | | | | | | |
| | KR | | | | | | | | | |

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

| | | | | |
|----|--|--|--|--|
| LR | Mattias Vangbo et al., High Precision Crystallographic Alignment of InP(100), Electrochemical and Solid-State Letters, 2(8) 1999, pp. 407-408. | | | |
| MR | G. Ensell, Alignment of mask patterns to crystal orientation, Sensors and Actuators A 53, (1996) pp. 345-348. | | | |
| NR | Mattias Vangbo et al., Precise mask alignment to the crystallographic orientation of silicon wafers using wet anisotropic etching, J. Micromech. Microeng. 6 (1996) pp. 279-284. | | | |
| OR | J. M. Lai et al., Precision alignment of mask etching with respect to crystal orientation, J. Micromech. Microeng. 8 (1998) pp. 327-329. | | | |
| PR | | | | |
| QR | | | | |

Examiner: *[Signature]* Date Considered: 4/11/2007

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.